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Radiation-Induced Current Transients in SiGe HBTs

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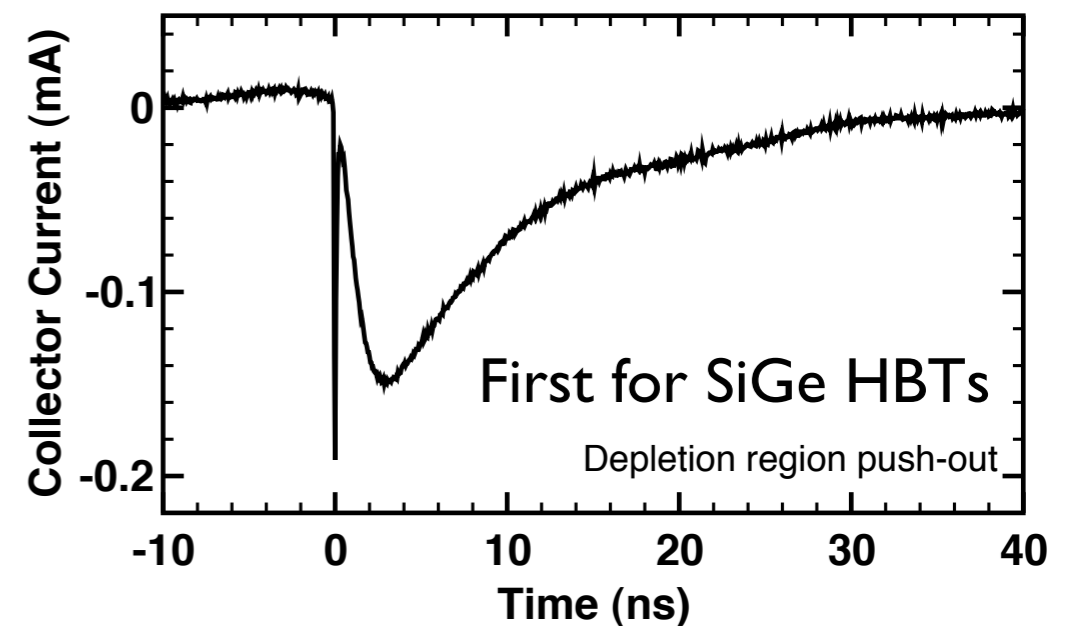
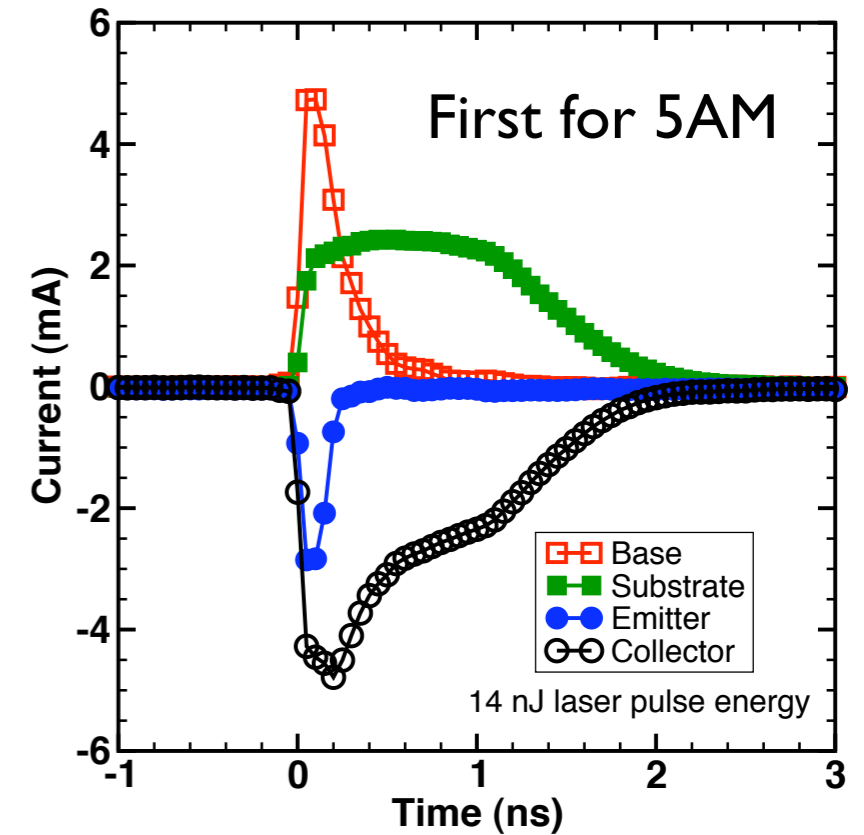
Acknowledgement

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 - DTRA Radiation Hardened Microelectronics Program
 - Naval Research Laboratory
- Thanks to the SiGe Team at IBM



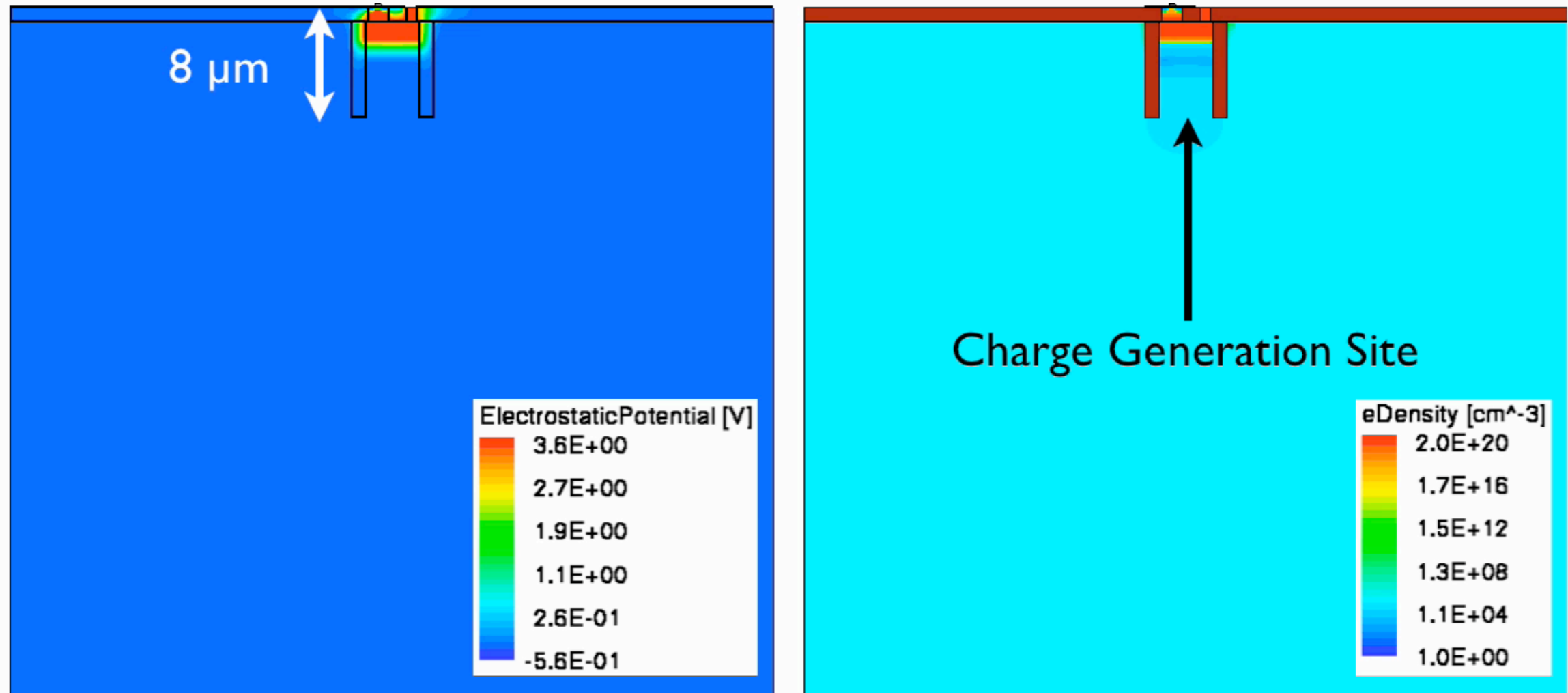
Presentation Synopsis

- Demonstrate need to measure current transients
- Describe relevant aspects of test vehicle: IBM 5AM SiGe HBT
- Utilize two-photon absorption as radiation source
- Validate heavy ion burst error data with measured transients
- Confirm substrate potential modulation in SiGe HBTs



SiGe HBT Substrate Potential Modulation

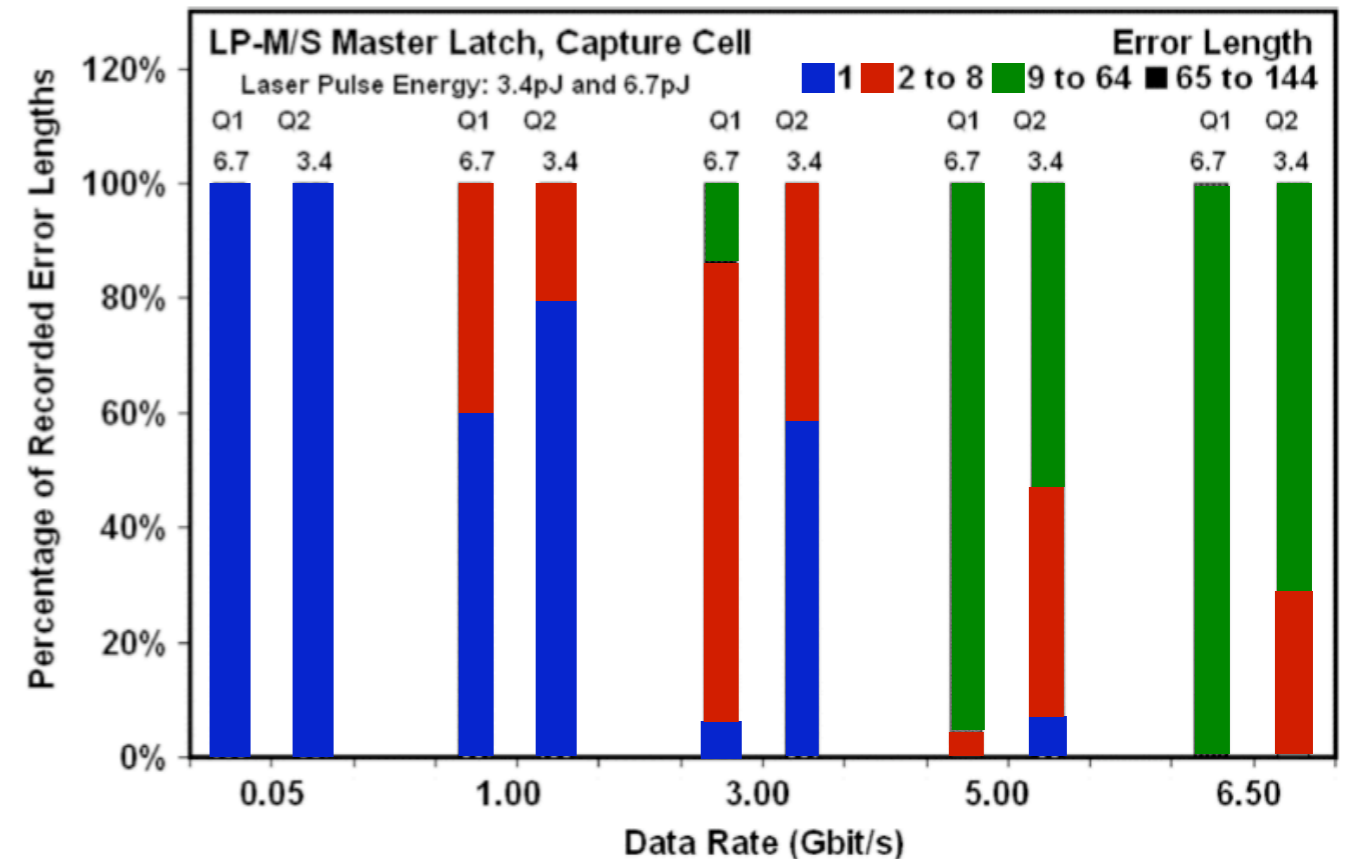
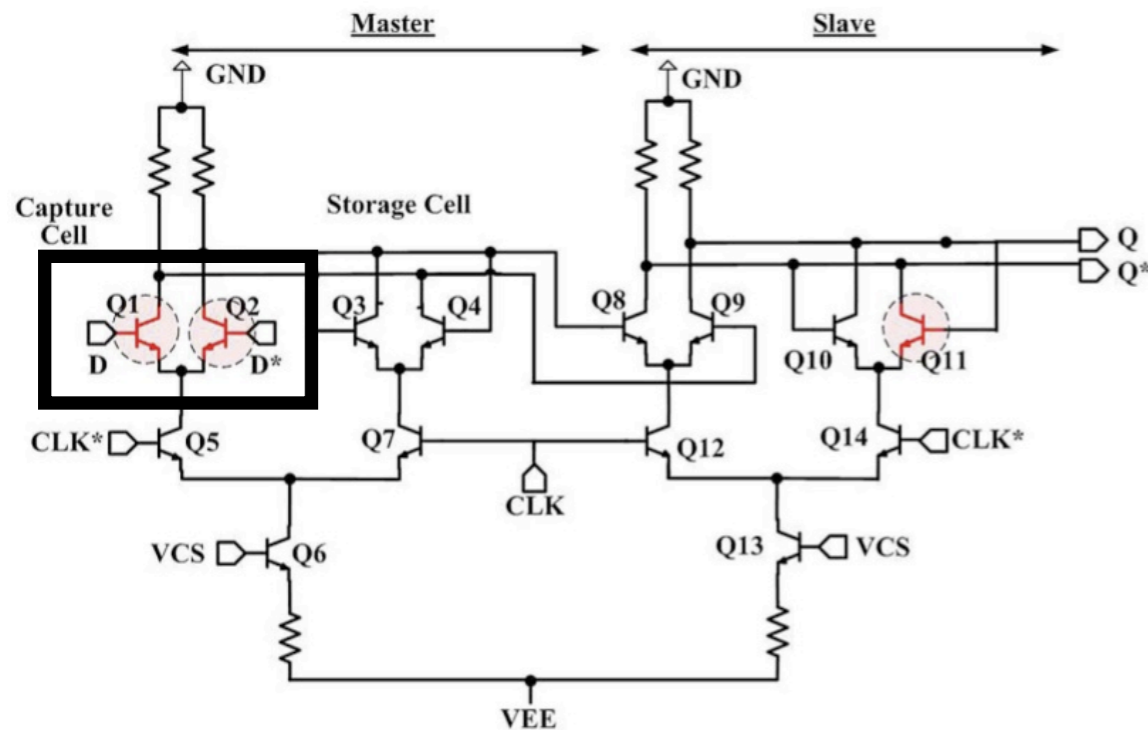
1.0×10^{-14} s



Setup is similar to laser-induced carrier generation



Time-Profile Matters: Laser-Induced Burst Errors

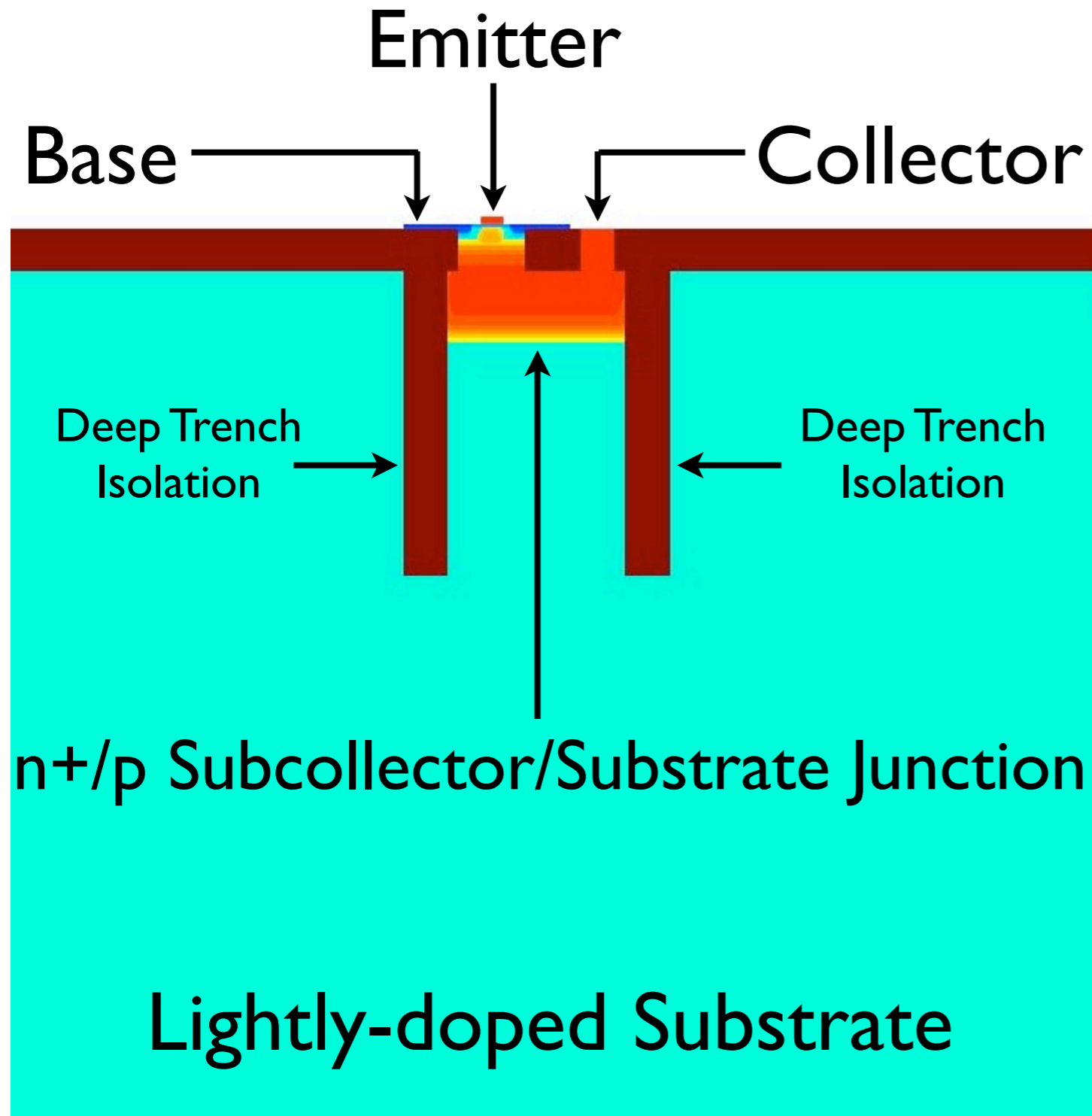


A. K. Sutton, et al., "SEU error signature analysis of Gbit/s SiGe logic circuits using a pulsed laser microprobe," *IEEE Trans. Nucl. Sci.*, vol. 53, pp. 3277-3284, Dec. 2006.

- Same laser pulse in all equal-energy cases
- Error length and composition changes with data rate
- Depends explicitly on current pulse characteristics



Radiation Relevant Features of SiGe HBTs



IBM 5AM SiGe HBT

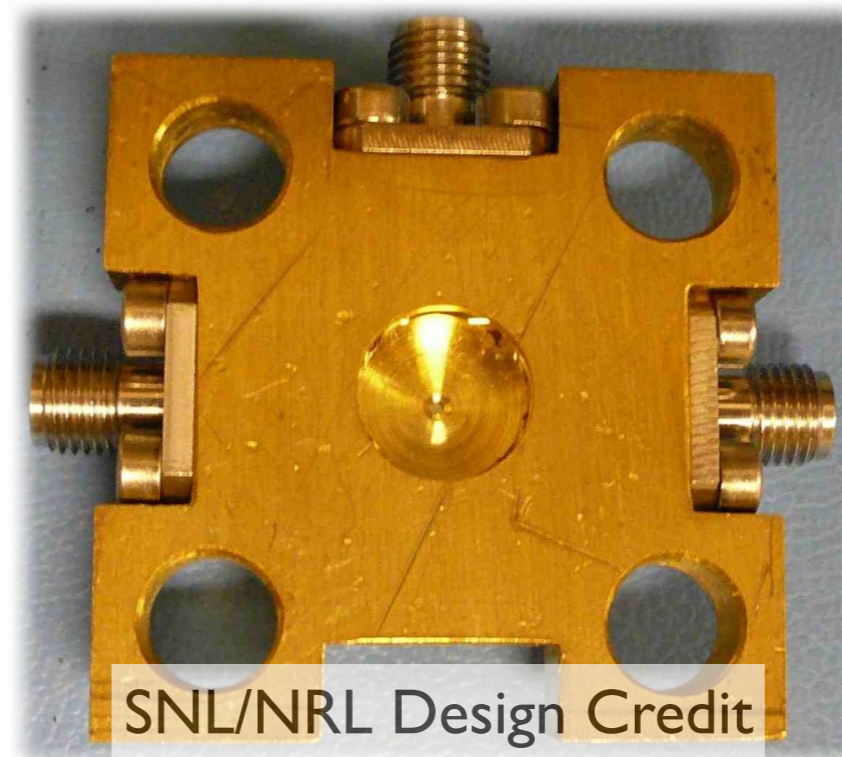
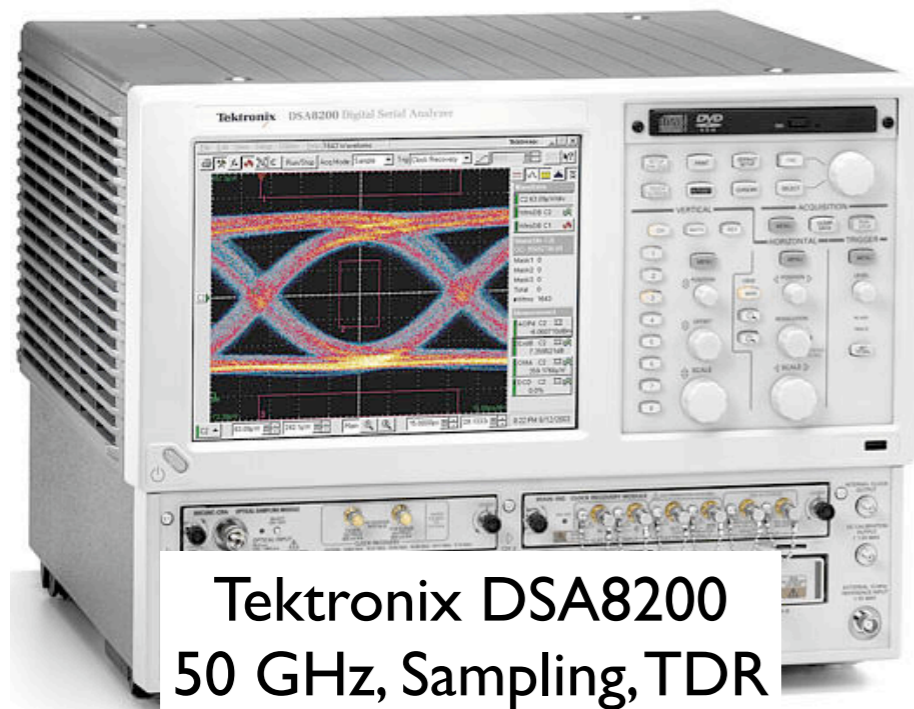
- Attention focused on the process features that dominate the single-event response
- Also the features that dominate the transient response



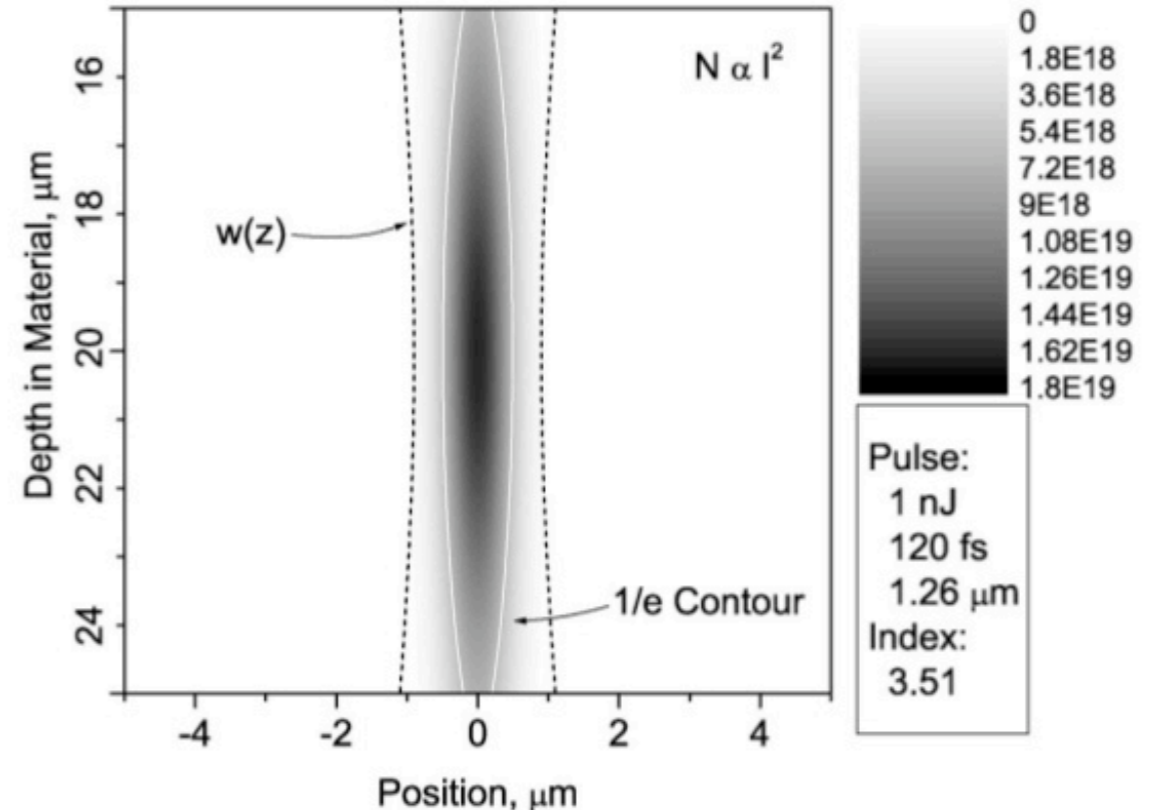
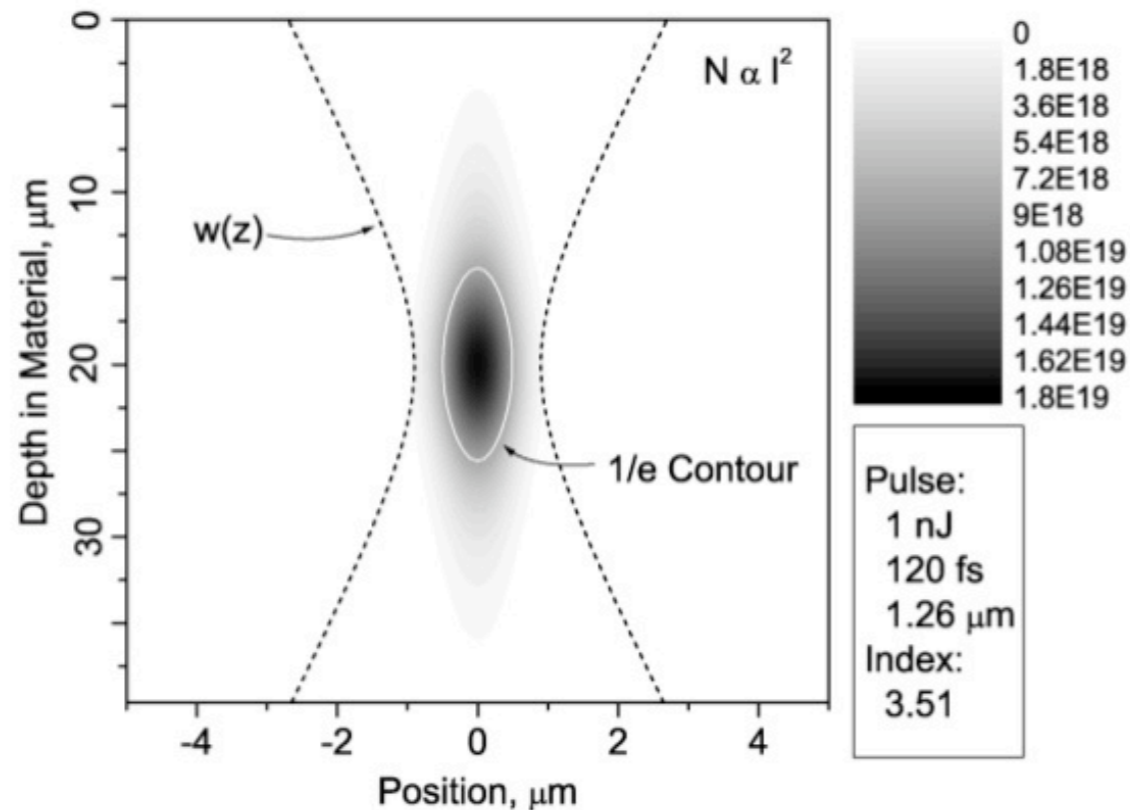
High-Speed Measurement Systems



←
40 GHz
2.92 mm
←



Two-Photon Absorption Generation

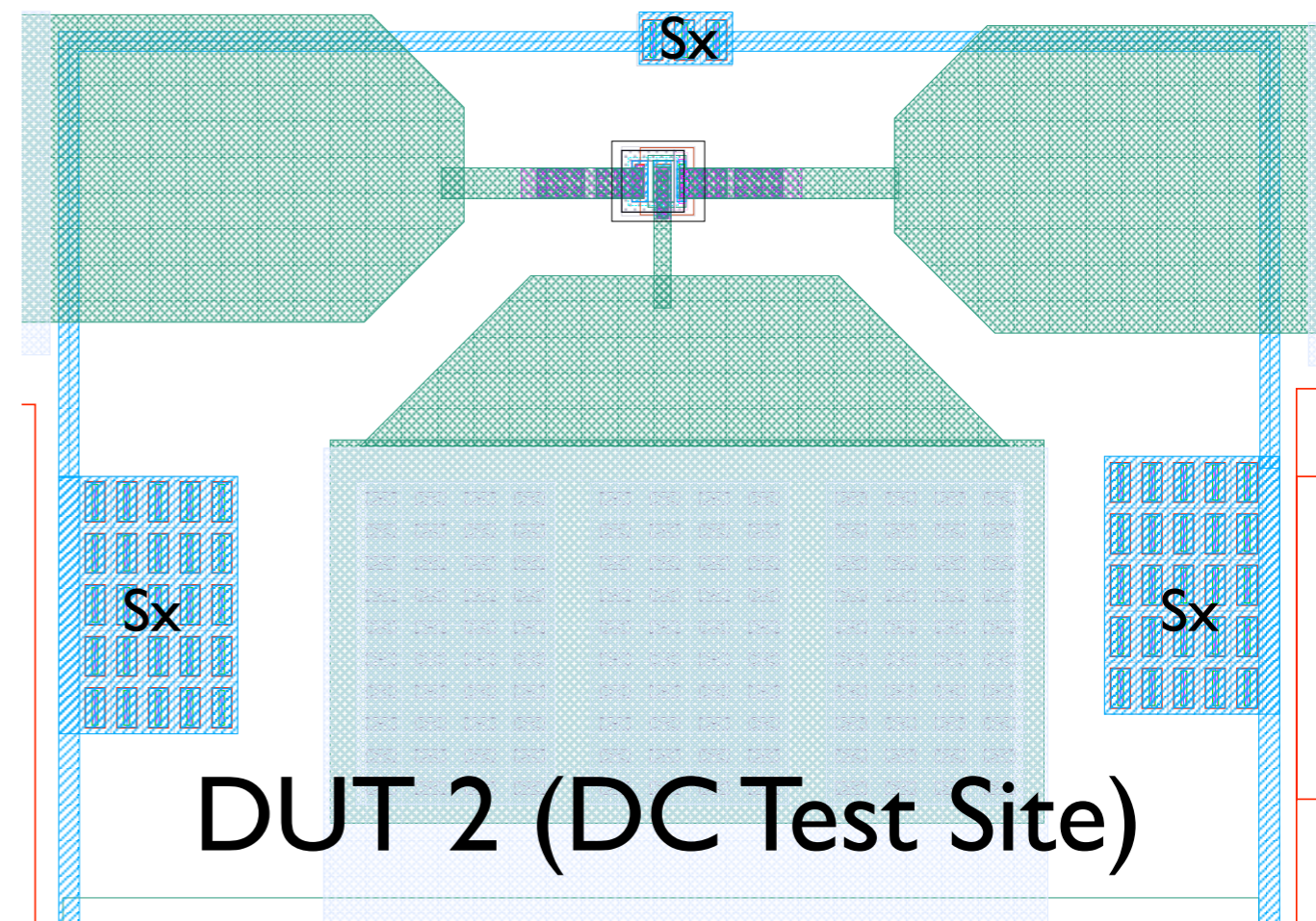
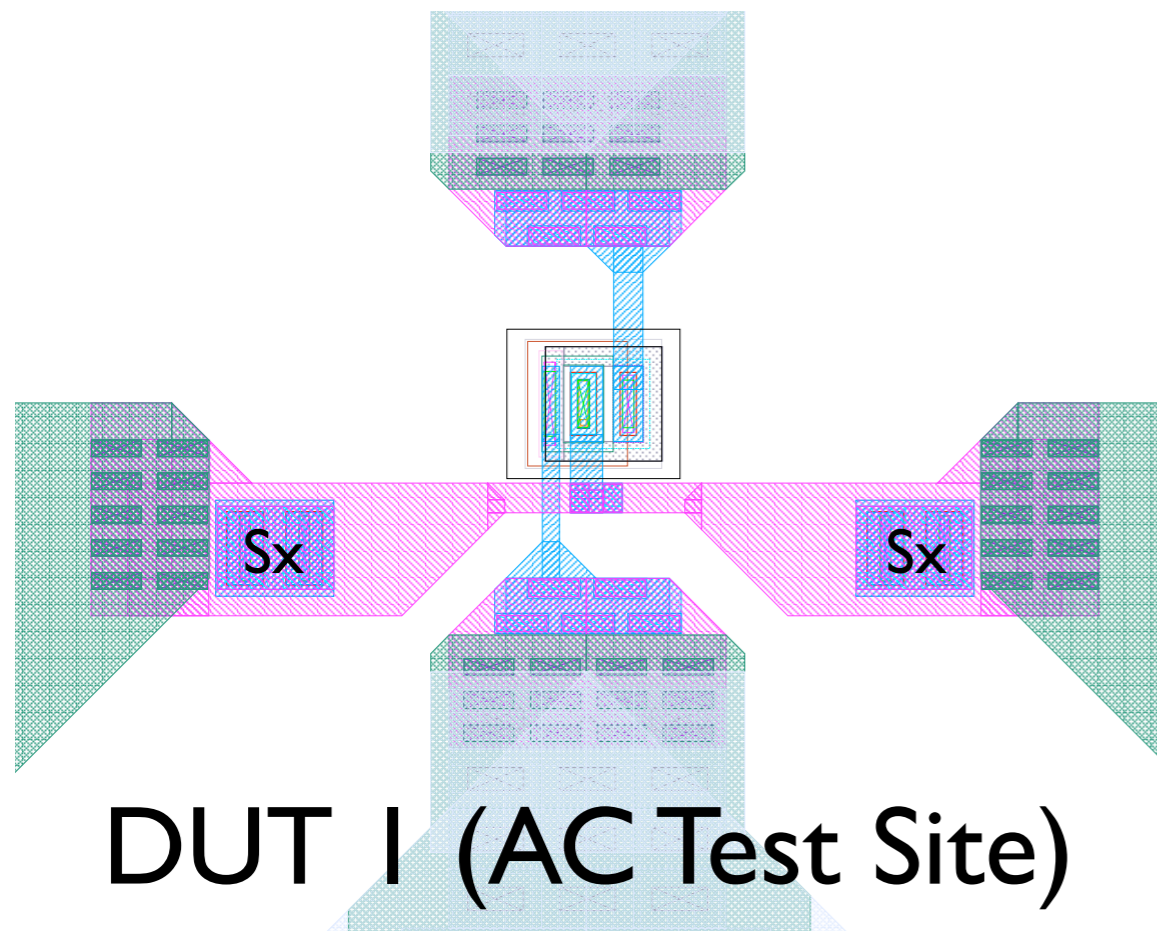


D. McMorrow, et al., "Subbandgap laser-induced single event effects: carrier generation via two-photon absorption," *IEEE Trans. Nucl. Sci.*, vol. 49, pp. 3002-3008, Dec. 2002.

- 1260 nm wavelength (non-linear absorption)
- Irradiate through the backside of the die (no BEOL)
- Allows for 3-D response mapping



SiGe HBT Devices Under Test

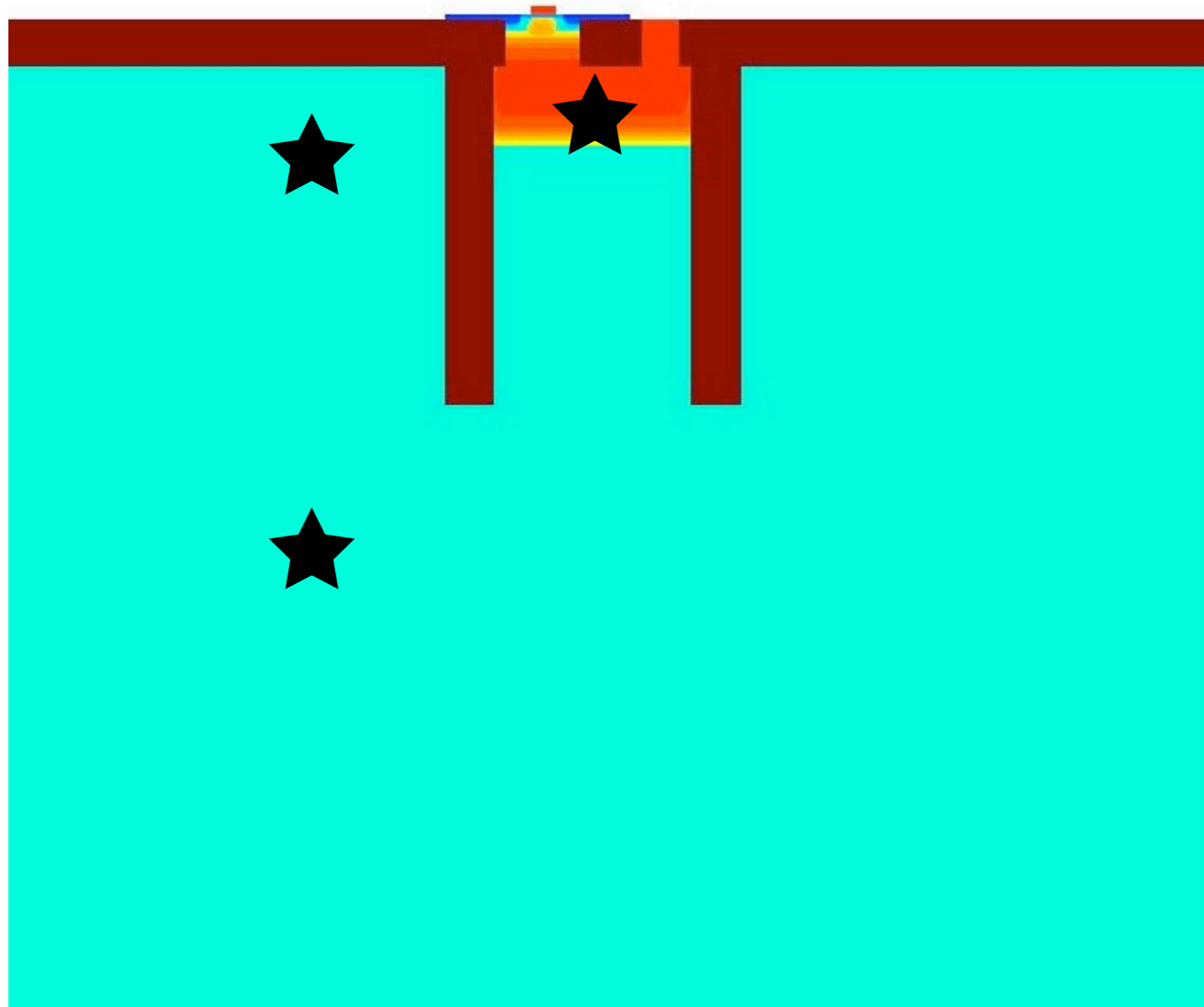


Drawings are not on the same scale

Same $0.5 \times 2.5 \mu\text{m}^2$ emitter geometry
Different substrate contact and metal routing schemes



Two-Photon Laser-Induced Transients



3 Strike Locations

DUT 1

3 V dropped across the subcollector junction

DUT 2

4 V dropped across the subcollector junction

All other terminals grounded

Data collected at the Naval Research Laboratory



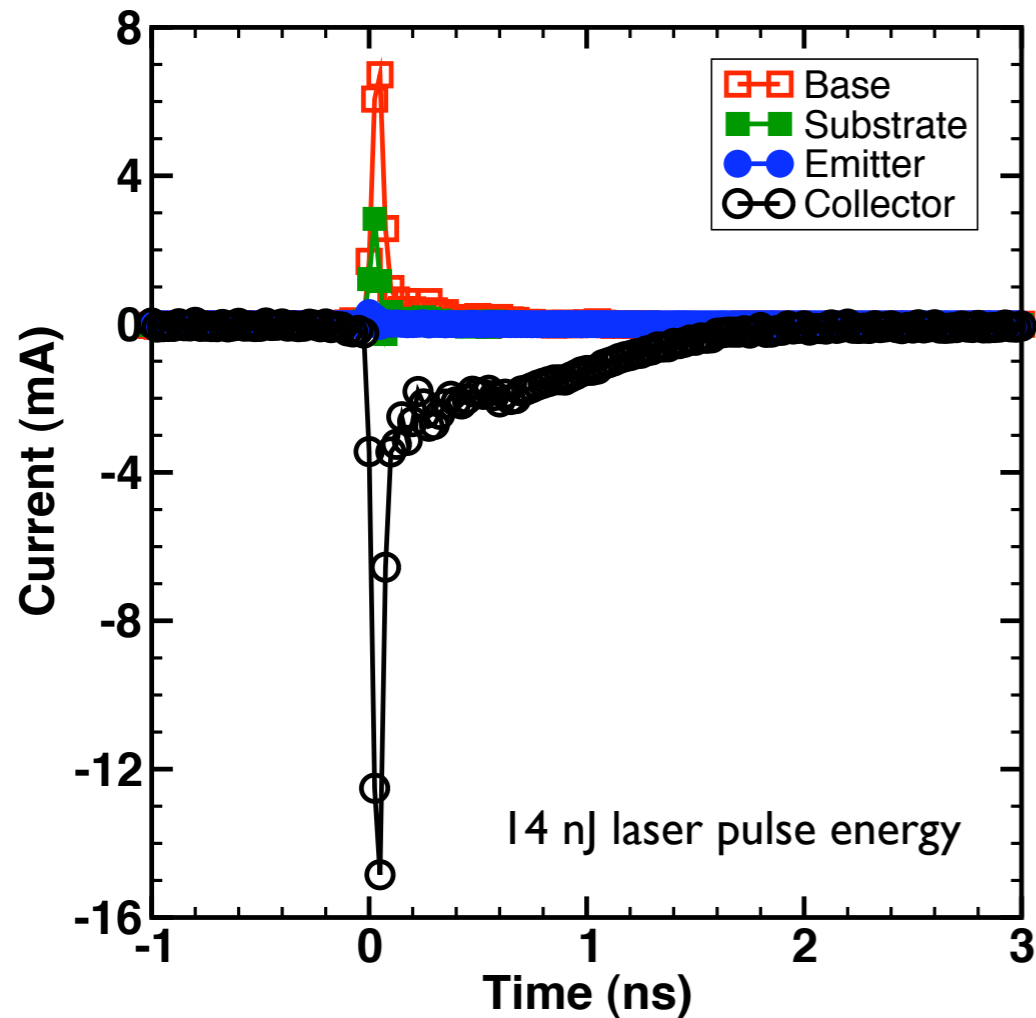
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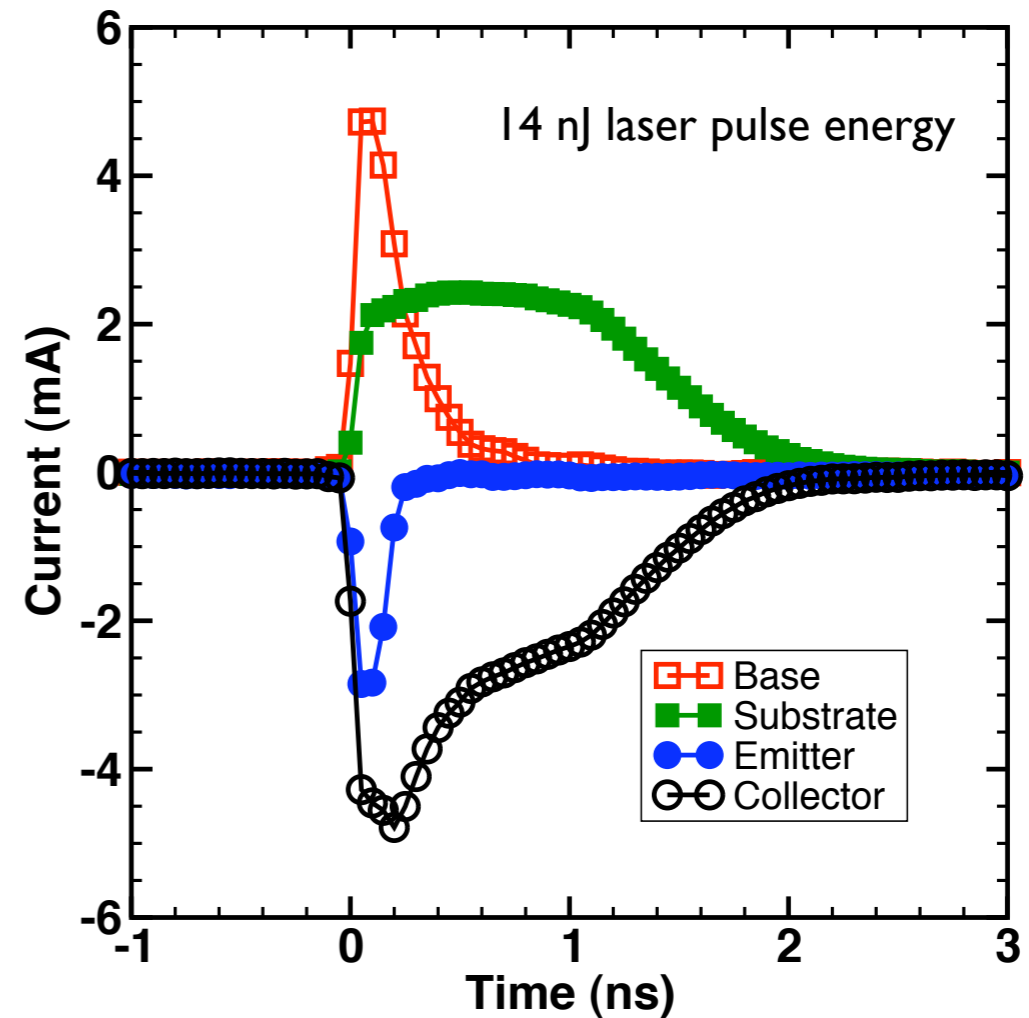
Jonathan A. Pellish

Two-Photon Laser-Induced Transients



DUT 1

Inside Trench

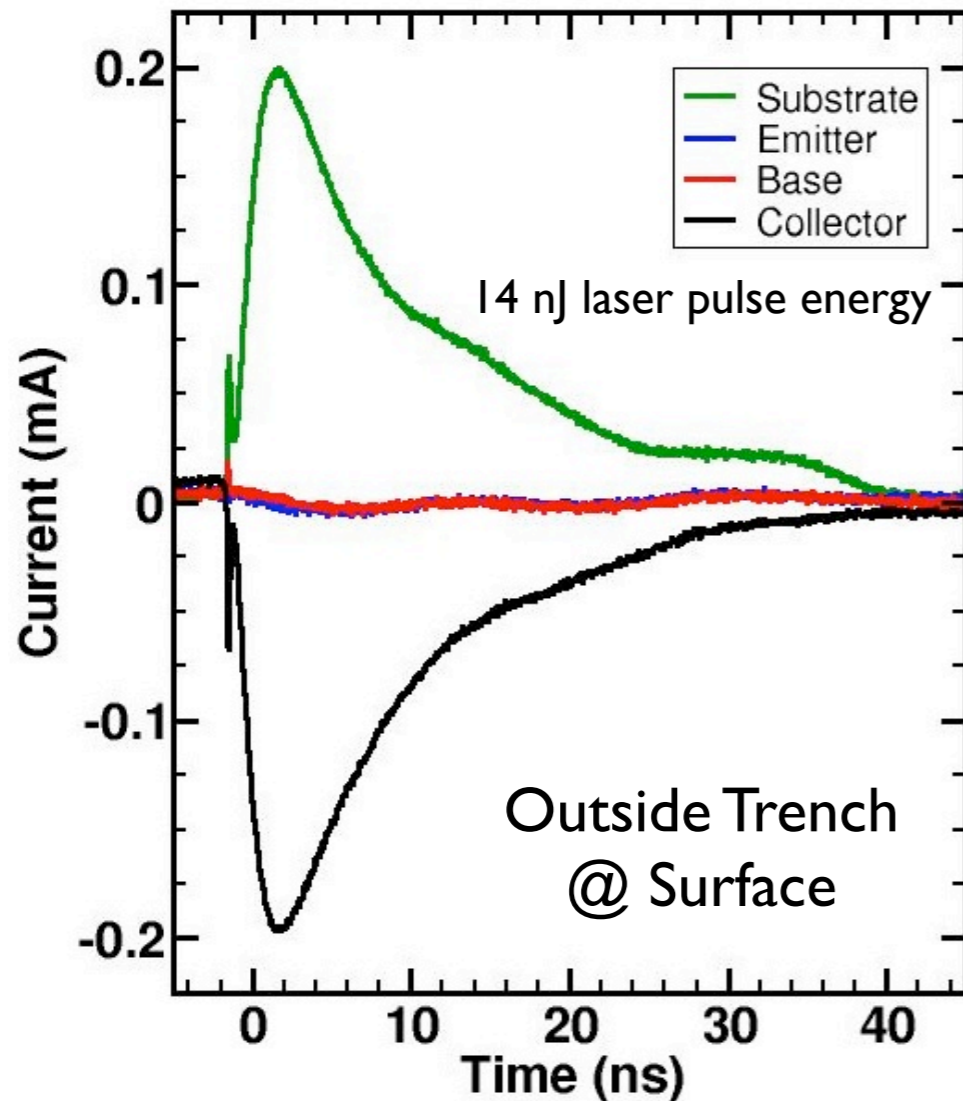


DUT 2

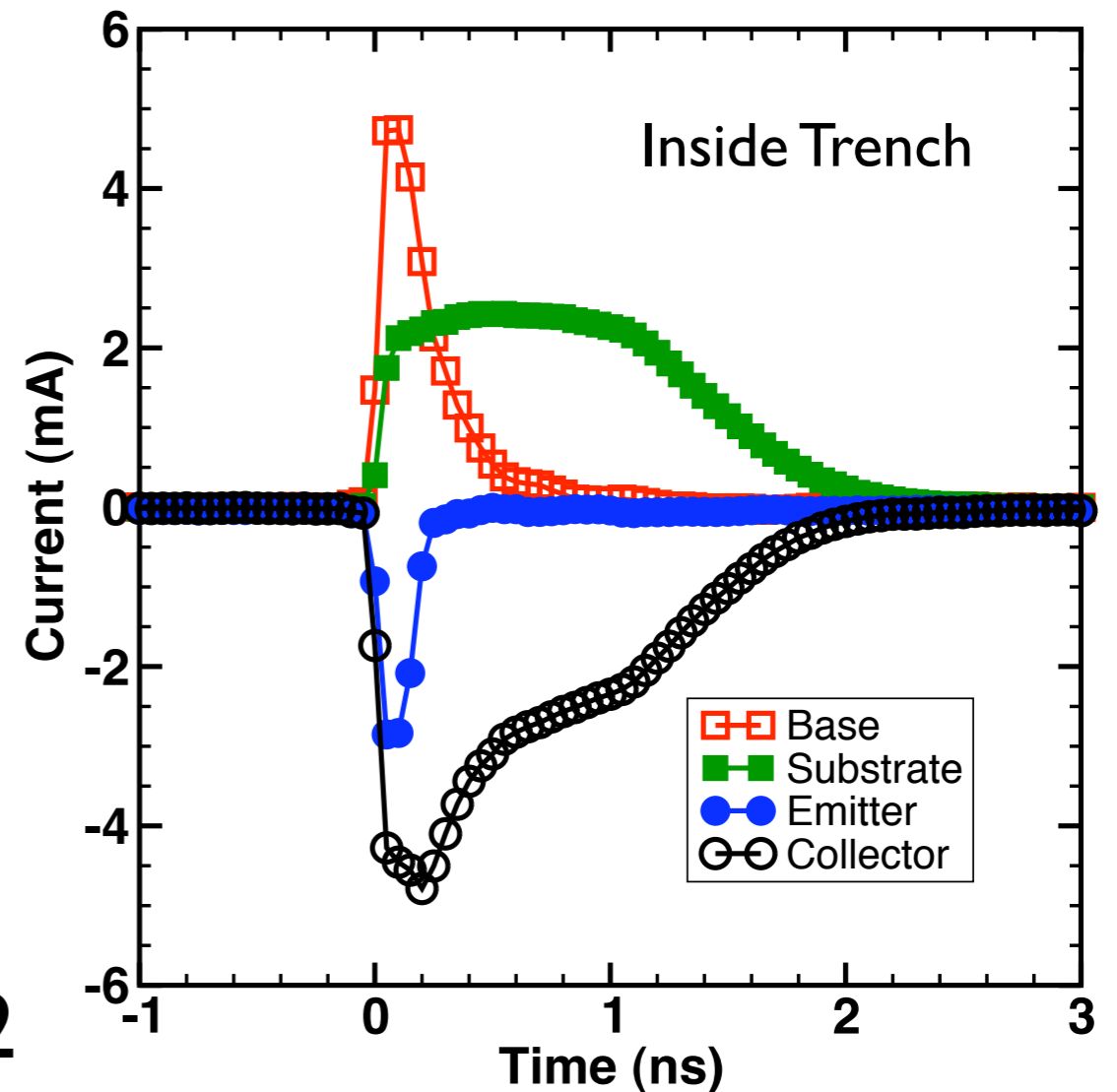
Compared to DUT 2, DUT 1 collector fall time is shorter by about 1.5x



Two-Photon Laser-Induced Transients



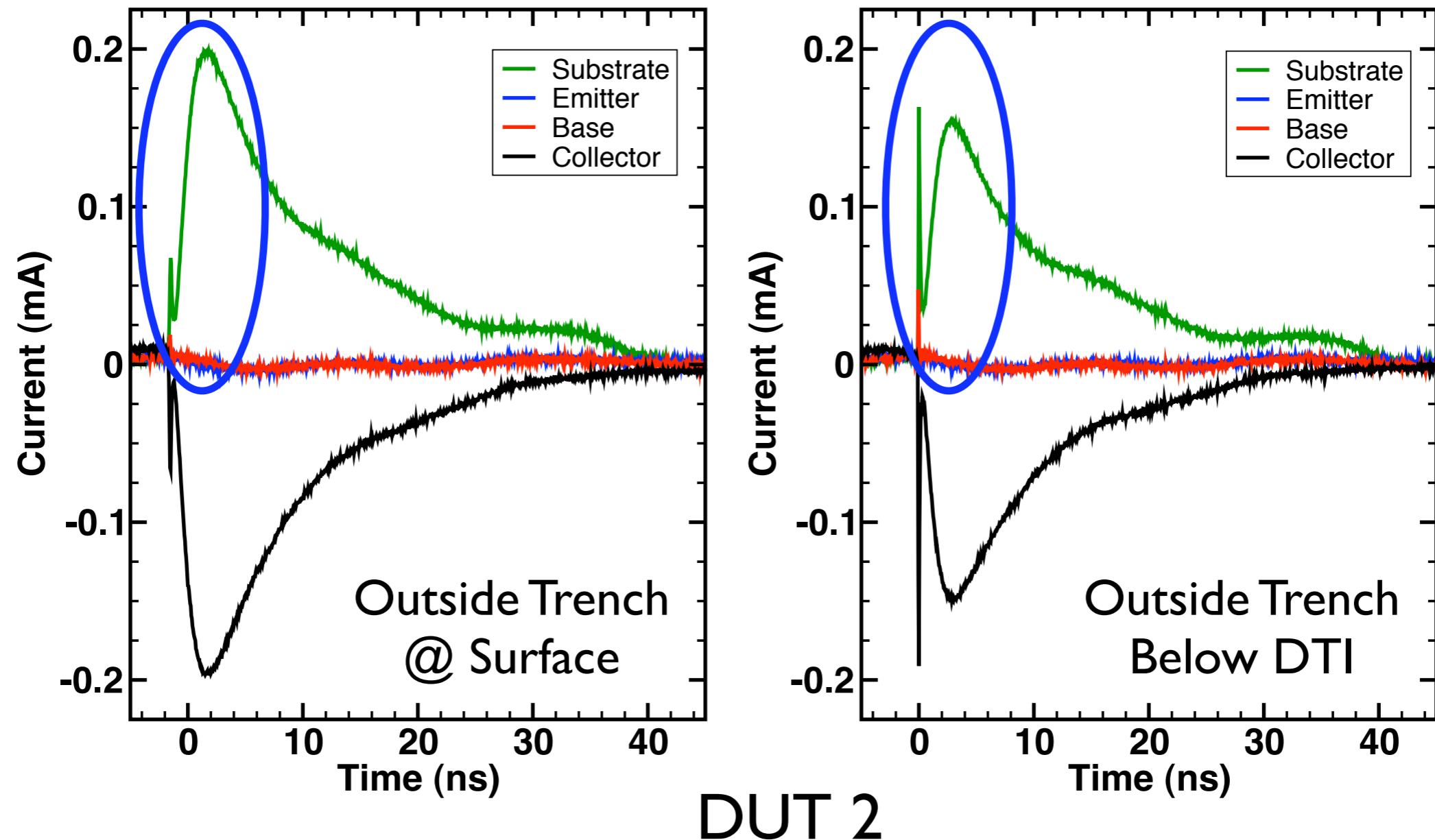
DUT 2



Transients originating outside the trench are consistent with diffusion processes (location- and energy-dependent)



Two-Photon Laser-Induced Transients



Measured evidence of substrate potential modulation



Conclusions

- The detailed characteristics of radiation-induced current transients are important for both high-speed and scaled technologies
- SiGe HBT radiation-induced transients are driven by the substrate doping, deep trench isolation, subcollector/substrate junction, and surrounding environment
- Substrate potential modulation in SiGe HBTs is a function of process, generation location, and energy

